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淡江大學104學年度日間部轉學生招生考試試題

系別: 化學學系三年級

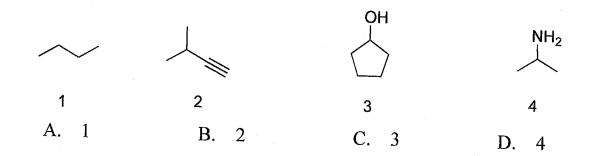
科目:有機化學

考試日期:7月26日(星期日)第3節

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- Multiple choice (40 pts, 2 pts each)
- 1. Which of the following structures contains an amine?



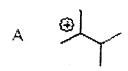
- 2. Which of the following compounds is the most acidic?

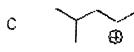
- D. NH_3

- 3. Which of the following cycloalkanes has the least angle strain?
 - A. Cyclopropane
- B. Cyclooctane
- C. Cyclohexane
- D. Cyclobutane
- 4. Which of the following is the correct IUPAC name for the following structure?



- (S)-3-ethyl-2-methylhexane
- B. (R)-3-ethyl-2-methylpentane
- (S)-3-ethyl-2-methylpentane
- D. (R)-3-ethyl-2-methylhexane
- 5. Which of the following cations is likely to undergo rearrangement?





D

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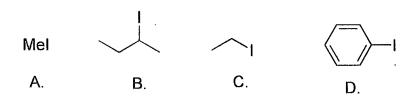
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6. Rank the following substrates from most to least reactive in an S_N2 reaction.



A. A>C>B>D

B. D>C>B>A

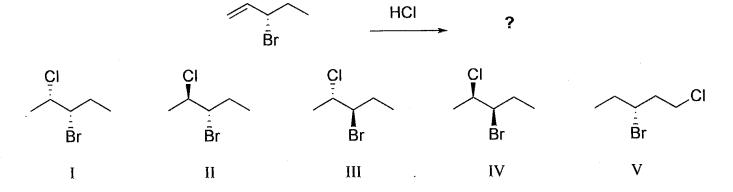
A>B>C>D

C.

D. D>A>B>C

7. Which of the following is the strongest nucleophile?

8. The expected major product(s) of HCl addition to the alkene shown would be:



A. I and II

B. II and III

C. I and IV

D. V

9. Rank the following bases, with the strongest base first, then by decreasing basicity.

HC
$$\equiv$$
C: CH $_3$ CH $_2$ O: CH $_3$ CH $_2$ H $_2$ N: H $_2$ C=CH

 $A. \qquad III > I > V > II > IV$

B. III > IV > II > V > I

C. V > I > III > II > IV

D. III > V > IV > I > II

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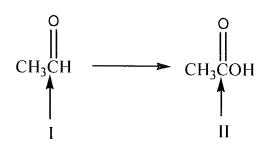
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10. What is the oxidation state of the carbon atoms I and II in the following reaction?

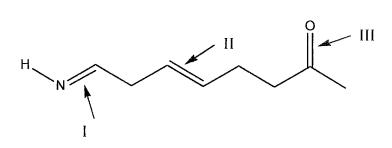


- A. I. +1, II. +2
- B.
- I. +2, II. +2
- C. I. +1, II. +3
- D. I. +3, II. +2

11. Which one of the following compounds will have the highest boiling point?

- CH₃CH₂CH₂CH₂CH₃ A.
- В. CH₃CH₂CH₂CH₂OH
- CH₃CH₂CH₂OCH₃
- D. CH₃CH₂OCH₂CHOH

12. Rank the indicated bonds in decreasing (highest to lowest) order of wavenumber.



- [[|>][>]
- B. I>II>III
-]]>]>]]]
- D. |||>||>||

13. Carboxylic acids show a very broad absorption for the OH compared to alcohols, because they can form a ____

- A.
- polymer B. dimer
- C. trimer
- D. tetramer

14. Which of the following is true about the number of signals in a ¹H NMR spectrum?

- it indicates the number of neighboring protons A.
- it indicates the electronic environment of neighboring protons B.
- C. it indicates the number of different kinds of protons
- it indicates the electronic environment of absorbing protons D.

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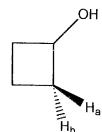
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15. Protons Ha and H_b in the following compound are



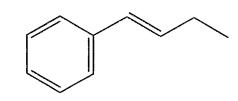
A. homotopic

B. enantiotopic

C. diastereotopic

D. mesotopic

16. How many signals would you expect to find in the ¹H NMR spectrum of the following compound?



A.

B. 8

C.

D. 6

17. Presence of which of the following protons is confirmed by D₂O exchange?

7

A. OH

B. C-H

C. NH₂

D. A & C

18. How many electrons does the HOMO of 1,3-pentadiene have in its excited state?

3

A. 1

B. 2

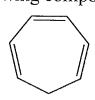
C.

D. 4

19. Which one of the following compounds is most acidic?



Α.



Ш

IV

I

B. II

C. III

D. IV

20. Predict the major product for the reaction between benzene and 2-chlorobutane in the presence of AlCl₃.

A. chlorobenzene

B. sec-butylbenzene

C. ethylbenzene

D. isopropylbenzene

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Provide the major product of each following reactions and indicate the stereochemistry if necessary. (30 pts, 2 pts each).

(a)

(b)

(c)

MeMgBr

(excess)

(e)

(f)

(h)

CO₂H

(i)

(1)

 H^{\dagger}

(m)

(n)

(0)

(p)

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III. Draw a stepwise, detailed mechanism for the following transformation. (10 pt)

IV. Synthesis the following compound A from benzene and any other organic or inorganic reagents. Show in detailed transformation. (10 pt)

$$NH_2$$
 CO_2H

V. Draw the most stable chair conformation of the following compound **A**. While compound **A** was treated with a strong base to undergo E2 elimination. What is the resulting major product? Explain. (10 pt)